IN THE SPECIFICATION:

The specification as amended below with replacement paragraphs shows added text with <u>underlining</u> and deleted text with <u>strikethrough</u>.

Please REPLACE the paragraph [0020] beginning at page 5, line 5, with the following paragraph:

[0020] A buffer pattern 280 is formed on the passivation film 270. The buffer pattern 270-280 smoothes a step difference between an anode electrode 290 above the substrate 200 and a step difference between a pixel define layer 300 and the substrate 200 such that a thickness of the electrode 290 above the substrate 200 is substantially the same as the pixel define layer 300 above the substrate 200. The anode electrode 290 is formed on the buffer pattern 280 in such a way that the anode electrode 290 is connected to one of the source/drain electrodes 281 and 285. For example, the anode electrode 290 is shown connected on the drain electrode 265 through a via hole 275. It is understood that the buffer pattern 280 need not be used in all aspects of the invention.